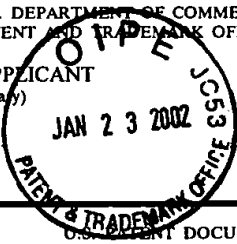


Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1427		SERIAL NO. 09/559,903		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Zhiping Yin et al. FILING DATE April 26, 2000 GROUP 2815				
FOREIGN DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
92	AA	0 942 330 A1	9/99	EPO	—	—		
91	AB	09-050993/JP9750993	2/97	Japan	—	—		
91	AC	406244172/6-244172	9/94	Japan	—	—		
91	AD	593,727	10/47	GB	—	—		
91	AE	5-263255/JP5263255	10/93	Japan	—	—		
91	AF	0 464 515 A3	1/92	EPO	—	—		
91	AG	0 771 886 A1	5/97	EPO	—	—		
91	AH	63-157443/JP63157443 A	6/88	JP	—	—		
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
94	AI	Robert Withnall et al., "Matrix Reactions of Methylsilanes and Oxygen Atoms", 1988 American Chemical Society, pp 594-602						
94	AJ	Weidman, T. et al., "New Photodefinable Glass Etch Masks for Entirely Dry Photolithography: Plasma Deposited Organosilicon Hydride Polymers", Appl. Phys. Lett., Vol. 62, No. 4, Jan. 25, 1993, pp. 372-374.						
94	AK	Weidman, T. et al., "All Dry Lithography: Applications of Plasma Polymerized Methylsilane as a Single Layer Resist and Silicon Dioxide Precursor", J. Photopolym. Sci. Technol., Vol. 8, No. 4, 1995, pp. 679-686.						
94	AL	Joubert, O. et al., "Application of Plasma Polymerized Methylsilane in an All Dry Resist Process for 193 and 248nm Lithography", Microelectronic Engineering 30 (1996), pp. 275-278.						
94	AM	Ajey M. Joshi et al; "Plasma Deposited Organosilicon Hydride Network Polymers as Versatile Resists for Entirely Dry Mid-Deep UV Photolithography"; SPIE Vol 1925/709; pp. 709-720						
94	AN	M. Matsuura et al.; "A Highly Reliable Self-planarizing Low-k Intermetal Dielectric for Sub-quarter Micron Interconnects"; IEEE 7/97 pp 31.6.1-31.6.4						
94	AO	O. Horie et al.; "Kinetics and Mechanism of the Reactions of O(P) with SiH ₄ , CH ₃ SiH ₃ , (CH ₃) ₂ SiH ₂ and (CH ₃) ₃ SiH", 1991 American Chemical Society, pp 4393-4400						
94	AP	McClatchie, S. et al., "Low Dielectric Constant Flowfill Technology for IMD Applications", Proceed. of 3d Internatl. Dielectrics for ULSI Multilevel Interconnection Conf, Santa Clara, CA, Feb. 1997, pp. 34-40.						
94	AQ	Beckman, K. et al., "Sub-Micron Gap Fill and In-Situ Planarisation Using Flowfill™ Technology", ULSI Conf, Portland, OR, Oct. 1995, pp. 1-7.						
94	AR	Kiermasz, A. et al., "Planarisation for Sub-Micron Devices Utilising a New Chemistry", DUMIC Conf., California, Feb. 1995, pp. 1-						
94	AS	IBM Technical Disclosure Bulletin "Low-Temperature Deposition of SiO ₂ , Si ₃ N ₄ or SiO ₂ -Si ₃ N ₄ ," Vol. 28, No. 9, p. 4170, Feb.						
94	AT	TEXT: Ralls, K. et al., "Introduction to Materials Science and Engineering", 1976 John Wiley & Sons, Inc., pp. 312-313.						
94	AU	ABSTRACT: Loboda, M. et al., "Using Trimethylsilane to Improve Safety, Throughput and Versatility in PECVD Processes", Electrochemical Society Meeting Abstract No. 358, 191 st Meeting, Montreal, Quebec, Vol. MA 97-1, 1997, page 454.						
94	AV	Laxman, R. et al., "Synthesizing Low-K CVD Materials for Fab Use", Semiconductor Internatl., Nov. 2000, pp. 95-102 (printed from www.semiconductor-intl.com).						
94	A	Anonymous, "New Gas Helps Make Faster ICs", Machine Design, Vol. 71, Iss. 21, Nov. 4, 1999, p. 118.						
94	AX	Julius Grant, "Hack's Chemical Dictionary", McGraw-Hill Book Company 1969, Fourth Edition, page 27.						
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92C Eherst				5/20/02				
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

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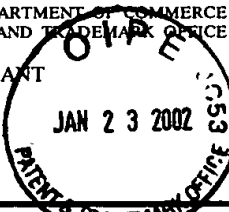


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JK	AA	4,474,975	10/84	Clemons et al.	556 410	
JK	AB	5,962,581	10/99	Hayase et al.	524 588	
JK	AC	5,677,015	10/97	Hasegawa	427 576	
JK	AD	5,783,493	7/98	Yeh et al.	438 118	
JK	AE	5,807,660	9/98	Lin et al.	430 313	
JK	AF	4,833,096	5/89	Huang et al.	438 201	
JK	AG	5,405,489	4/95	Kim et al.	438 698	
JK	AH	5,470,772	11/95	Woo	438 588	
JK	AI	5,652,187	7/97	Kim et al.	438 760	
JK	AJ	5,656,337	8/97	Park et al.	427 539	
JK	AK	4,805,683	2/89	Magdo et al.	216 40	
JK	AL	5,874,367	2/99	Dobson	438 787	
JK	AM	5,858,880	1/99	Dobson et al.	438 758	
JK	AN	5,219,613	6/93	Fabry et al.	438 758	
JK	AO	5,270,267	12/93	Ouellet	438 597	
JK	AP	5,541,445	7/96	Ouellet	438 761	
JK	AQ	6,022,404	2/00	Ettlinger et al.	106 404	
JK	AR	5,709,741	1/98	Akamatsu et al.	106 287.11	
JK	AS	4,648,904	3/87	Depasquale et al.	106 2	
JK	AT	4,158,717	6/79	Nelson	428 446	
JK	AU	5,667,015	9/97	Harestad et al.	166 383	
JK	AV	5,661,093	8/97	Ravi et al.	438 763	
JK	AW	5,536,857	7/96	Narula et al.	556 10	
JK	AX	4,695,859	9/87	Guha et al.	257 64	

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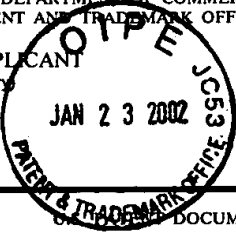


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92	AA	5,061,509	10/91	Naito et al.	427	497	
92	AB	4,600,671	7/86	Saitoh et al.	430	57.5	
92	AC	5,753,320	5/98	Mikoshiba et al.	427	572	
92	AD	5,356,515	10/94	Tahara et al.	438	715	
92	AE	6,054,379	4/00	Yau et al.	438	623	
92	AF	5,948,482	9/99	Brinker et al.	516	33	
92	AG	5,800,877	9/98	Maeda et al.	427	535	
92	AH	5,260,600	11/93	Harada	257	639	
92	AI	4,992,306	2/91	Hochberg et al.	427	255.29	
92	AJ	4,702,936	10/87	Maeda et al.	427	583	
92	AK	4,863,755	9/89	Hess et al.	427	574	
92	AL	5,234,869	8/93	Mikata et al.	438	793	
92	AM	5,302,366	4/94	Schuetz et al.	423	346	
92	AN	5,591,494	1/97	Sato et al.	427	579	
92	AO	5,968,611	10/99	Kaloyeros et al.	427	579	
92	AP	6,159,871	12/00	Loboda et al.	438	786	
92	AQ	5,461,003	10/95	Havemann et al.	438	666	
92	AR	6,124,641	9/00	Matsuura	257	759	
92	AS	5,554,567	9/96	Wang	438	624	
92	AT	6,028,015	2/00	Wang et al.	438	789	
92	AU	5,744,399	4/98	Rostoker et al.	438	622	
92	AV	5,883,014	3/99	Chen et al.	438	782	
92	AW	6,017,779	1/00	Miyasaka	438	149	
92	AX	6,156,674	12/00	Li et al.	438	780	

EXAMINER <i>92 Schubert</i>	DATE CONSIDERED 5/20/02
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gk	AA	6,140,151	10/00	Akram	438	113	
gk	AB	5,314,724	5/94	Tsukune et al.	427	489	
de	AC	5,376,591	12/94	Maeda et al.	438	761	
de	AD	5,817,549	10/98	Yamazaki et al.	438	166	
gk	AE	6,072,227	6/00	Yau et al.	257	642	
gk	AF	6,001,741	12/99	Alers	438	706	
gk	AG	5,786,039	7/98	Brouquet	427	578	
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gk	AI	6,187,694	2/01	Cheng et al.	438	142	
gk	AJ	5,750,442	5/98	Juengling	438	761	
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gk	AL	6,238,976	5/01	Noble et al.	438	259	
gk	AM	6,008,121	12/99	Yang et al.	438	637	
gk	AN	5,140,390	8/92	Li et al.	257	350	
gk	AO	5,286,661	2/94	de Fresart et al.	438	343	
gk	AP	6,184,151	2/01	Adair et al.	438	743	
gk	AQ	6,225,217 B1	5/01	Usami et al.	438	637	
gk	AR	6,004,850	12/99	Lucas et al.	438	301	
gk	AS	6,140,677	10/00	Gardner et al.	257	327	
gk	AT	6,133,096	10/00	Su et al.	438	264	
gk	AU	6,136,636	10/00	Wu	438	231	
gk	AV	5,933,721	8/99	Hause et al.	438	217	
gk	AW	5,981,368	11/99	Gardner et al.	438	217	
gk	AX	6,159,804	12/00	Gardner et al.	438	265	
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DOCUMENTS							
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94	AA	6,130,168	10/00	Chu et al.	439	717	
94	AB	6,235,591	5/01	Balasubramanian et al.	438	275	
94	AC	6,198,144 B1	3/01	Pan et al.	257	42	
	AD						
	AE						
94	AF	App. 09/146,843 (as filed and amended)		Li et al.			9/98
94	AG	App. 09/234,233 (as filed and amended)		Li et al.			9/98
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→ OTHER REFERENCES

Form PTO-1499		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. M122-1427		SERIAL NO. 09/559,903	
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					APPLICANT Zhiping Yin et al.		FILING DATE April 26, 2000	
U.S. PATENT DOCUMENTS								
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate		
JSE	AA	07/2001	Sandhu et al.	438	636			
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
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